

WHAT IS CLAIMED IS:

1. A cleaning sheet comprising a cleaning layer and a releasable protective film laminated on the cleaning layer, wherein each of the relative intensities of the fragment ions of CH_3Si^+ , $\text{C}_3\text{H}_9\text{Si}^+$, $\text{C}_5\text{H}_{15}\text{Si}_2\text{O}^+$, $\text{C}_5\text{H}_{15}\text{Si}_3\text{O}_3^+$, $\text{C}_7\text{H}_{21}\text{Si}_3\text{O}_2^+$, CH_3SiO^- , $\text{CH}_3\text{SiO}_2^-$ and Si^+ in the cleaning layer, when the protective film is peeled off the cleaning layer, is 0.1 or less according to time-of-flight secondary ion mass spectrometry, relative to C_2H_3^+ in the case of positive ion or O^- in the case of negative ion.
2. The cleaning sheet according to claim 1, wherein the cleaning layer has substantially no adhesive strength.
3. The cleaning sheet according to claim 1 or 2, which further comprises a support, wherein the cleaning layer is provided on the support.
4. The cleaning sheet according to claim 3, which further comprises an adhesive layer provided on the side opposite to the adhesive layer, wherein the support has the cleaning layer provided on one side thereof.

5. A carrying member with a cleaning function, comprising a carrying member and a cleaning sheet defined in claim 4 laminated on the carrying member through an adhesive layer.

6. The cleaning sheet according to any one of claims 1, 2 and 4, wherein the cleaning layer comprises a heat-resistant polymer resin.

7. The carrying member according to claim 5, wherein the cleaning layer comprises a heat-resistant polymer resin.

8. A carrying member with a cleaning function, comprising a carrying member and a cleaning layer provided on at least one side of the carrying member, wherein each of the relative intensities of the fragment ions of CH_3Si^+ , $\text{C}_3\text{H}_9\text{Si}^+$, $\text{C}_5\text{H}_{15}\text{Si}_2\text{O}^+$, $\text{C}_5\text{H}_{15}\text{Si}_3\text{O}_3^+$, $\text{C}_7\text{H}_{21}\text{Si}_3\text{O}_2^+$, CH_3SiO^- , $\text{CH}_3\text{SiO}_2^-$ and Si^+ in the cleaning layer is 0.1 or less according to time-of-flight secondary ion mass spectrometry, relative to C_2H_3^+ in the case of positive ion or O^- in the case of negative ion.

9. The carrying member according to claim 8, wherein the cleaning layer has substantially no adhesive strength.

10. The carrying member according to claim 8 or 9, wherein the cleaning layer comprises a heat-resistant polymer resin.

11. A carrying member with a cleaning function, comprising a carrying member and a cleaning layer provided on at least one side of the carrying member, wherein the time required until the degree of vacuum in a chamber which has been temporarily reduced from 3×10^{-10} torr when the carrying member is put therein at a temperature of 50°C is returned to 1×10^{-9} torr is 100 minutes or less after putting the carrying member in the chamber.

12. The carrying member with a cleaning function according to claim 11, wherein the cleaning layer has substantially no adhesive strength.

13. The carrying member with a cleaning function according to claim 11 or 12, wherein the cleaning layer comprises a heat-resistant polymer resin.

14. The carrying member with a cleaning function according to claim 11 or 12, which further comprises a support, wherein the support has the cleaning layer provided on one side thereof and an adhesive layer provided on the other thereof

and the cleaning layer is provided on the carrying member through the adhesive layer.

15. A method of cleaning a substrate processing equipment which comprises conveying a cleaning sheet defined in claim 1, or a carrying member with a cleaning function defined in any one of claims 5, 8 and 11 into a substrate processing equipment.

16. A substrate processing equipment cleaned by a cleaning method defined in claim 15.